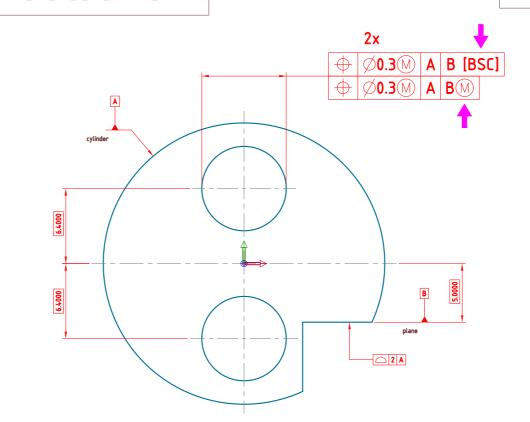
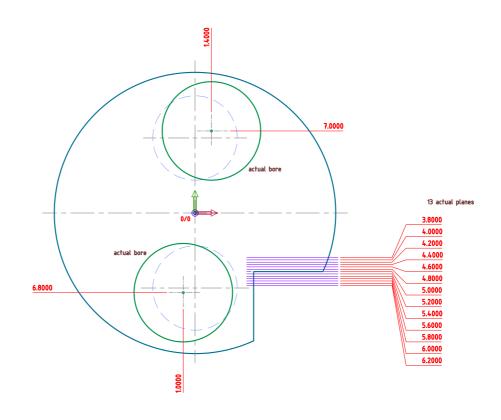
True Position and datum AB

Dimensioning

Pic. #1

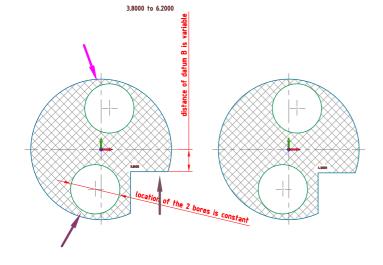


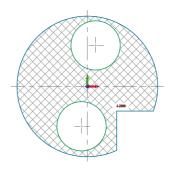
Actual situation

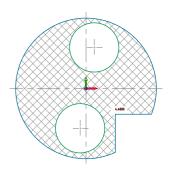


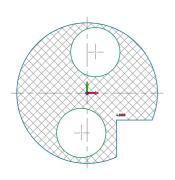


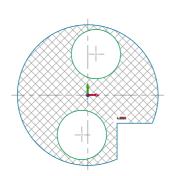


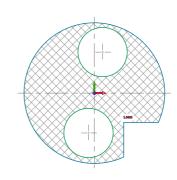


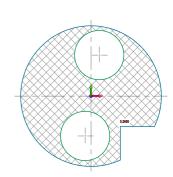


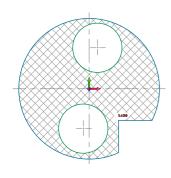


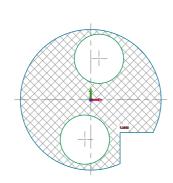


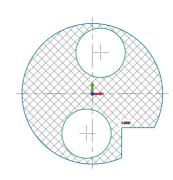


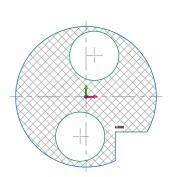


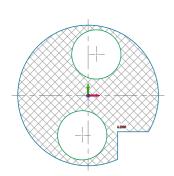










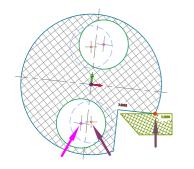


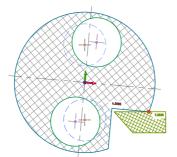
Same 0000

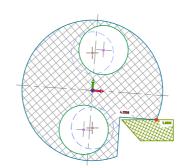
Pic. #3

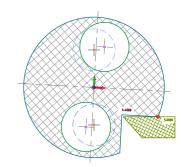
Datum B simulator at 5.0000

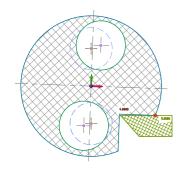


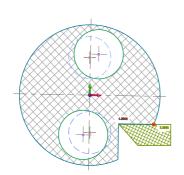


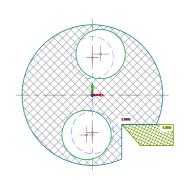


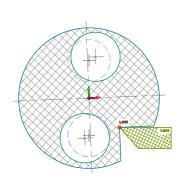


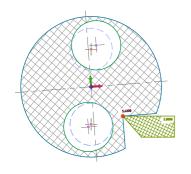


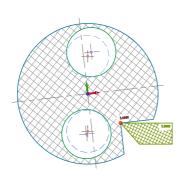


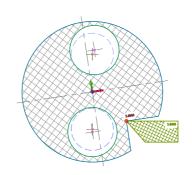


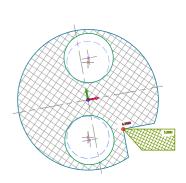


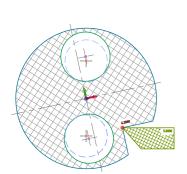


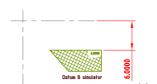








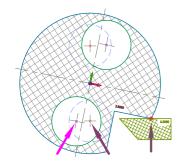


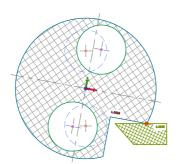


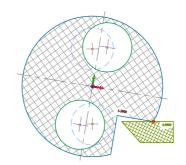
Pic. #4

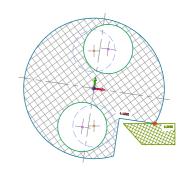
Datum B simulator at 6.0000

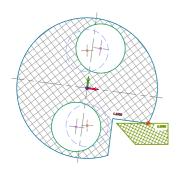


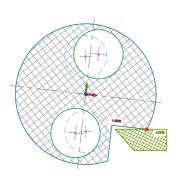


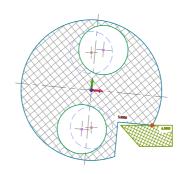


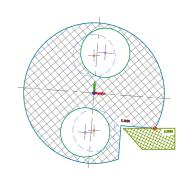


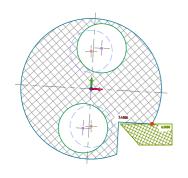


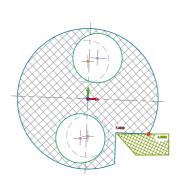


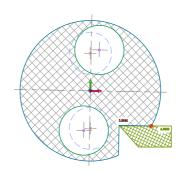


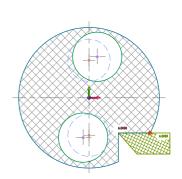


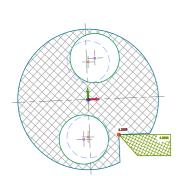


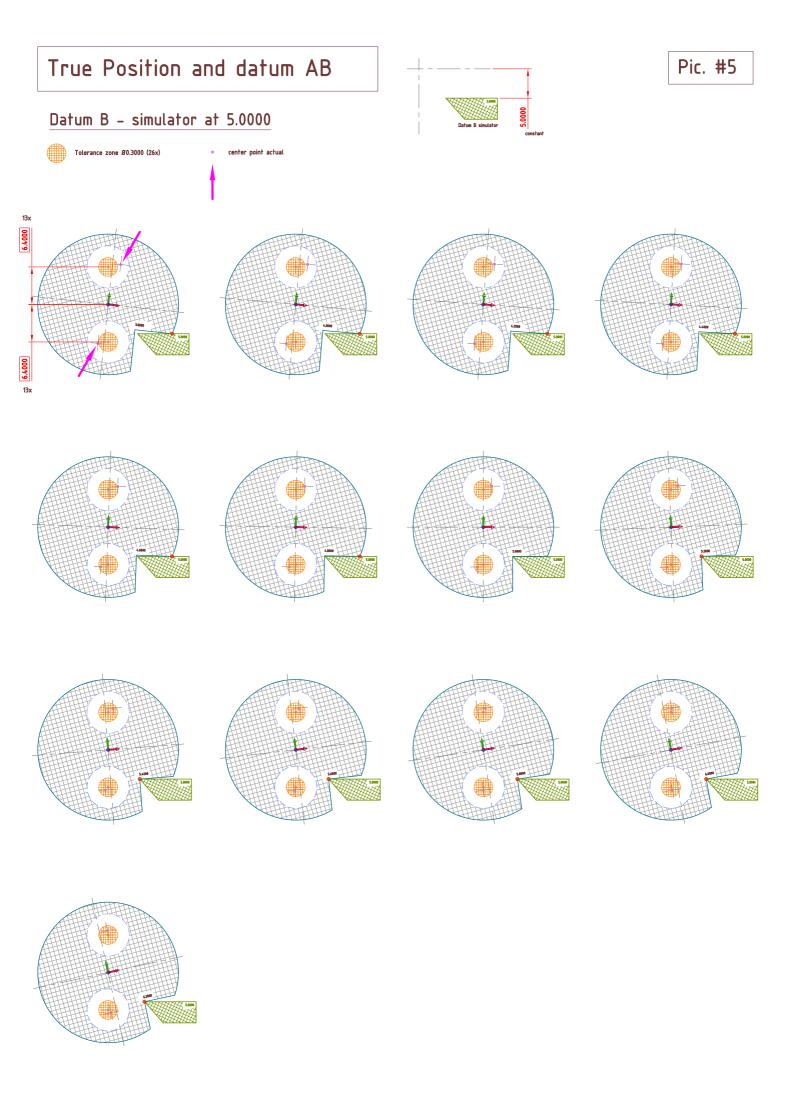


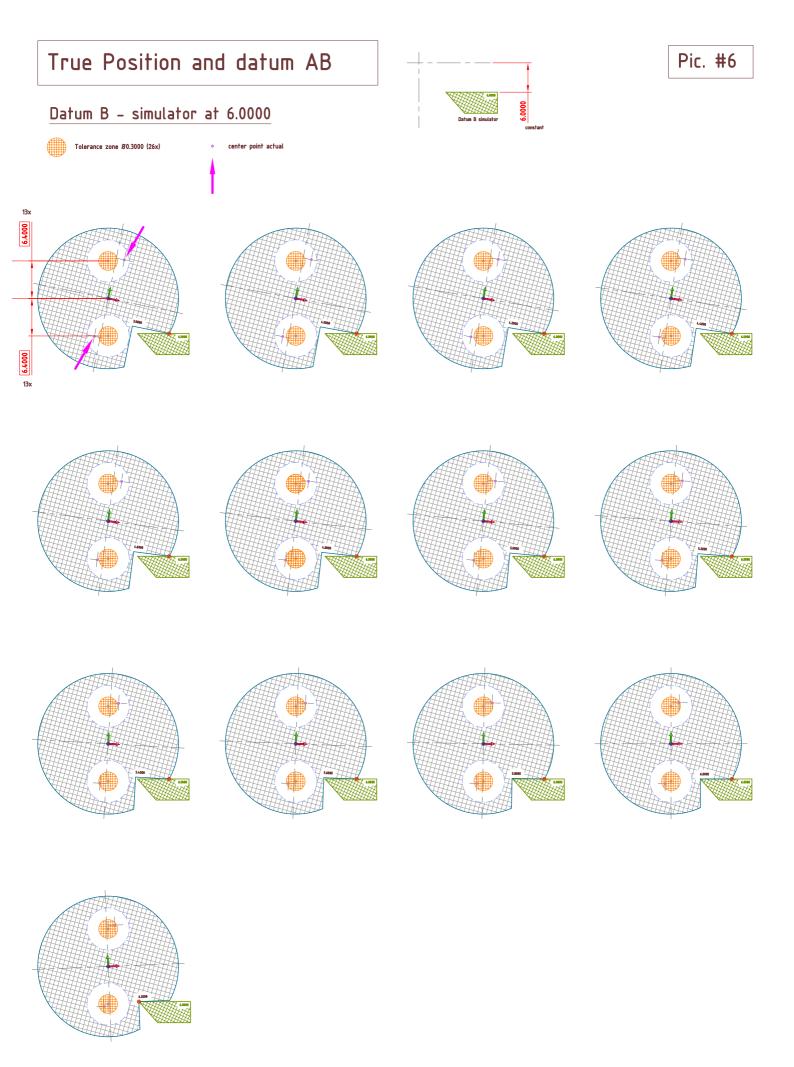












Datum B - simulator at 5.0000

⊕ Ø0.3M A B [BSC]

5.0000

Datum B simulator

Datum B - simulator at 6.0000

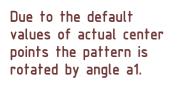
5.0000

1.0000

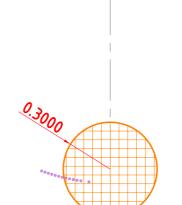
6.0000 Datum B simulator

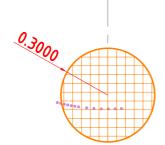






Due to the "MM-size" 6.0000 the pattern is rotated by angle a1 and angle a2.
There is no technical reason for admitting such a phenomenon.





Datum B - simulator at 5.0000

 $| \oplus | \emptyset$ 0.3M | A | B [BSC]

5.0000

Datum B simulator



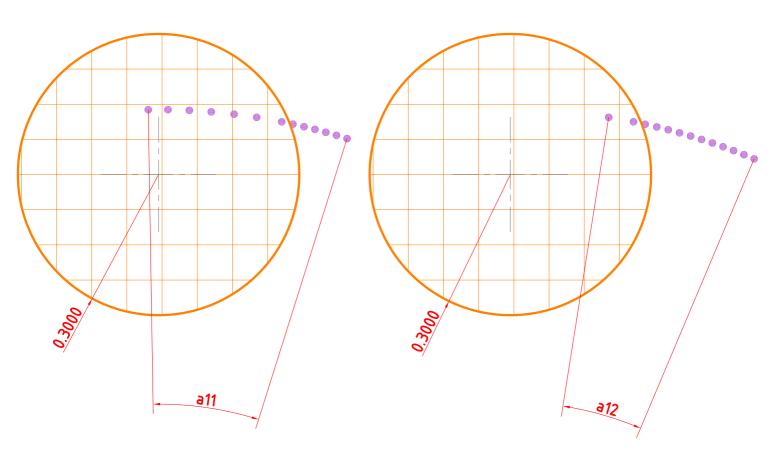
Datum B - simulator at 6.0000

5.0000

1.0000

6.0000 Datum B simulator





Angle a11 > angle a12:

significant "Tolerance Benefit" caused by the changeable one-point-touchment at the datum B-simulator.

Angle a12 < angle a11:

reduced "Tolerance Benefit" in spite of MMC on datum B. MMC obviously only leads to an unintended "rotatory offset".





